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Abstract

The present invention relates to a method for fabricating a probe tip, including the steps of: patterning a photoresist having a predetermined size formed at a upper surface of a substrate, where a probe tip is to be formed, and performing an anisotropic etching on the substrate to a part of a height of the probe tip by using the patterned photoresist as an etching mask; removing the patterned photoresist, patterning another photoresist covering the etched area of the substrate, and performing an anisotropic etching on the substrate to the height of the probe tip by using the patterned photoresist as an etching mask; removing the patterned photoresist and performing an oxidation process on the substrate to thereby form an oxide film on the whole surface thereof; and removing the oxide film by wet-etching the oxide file using a mixed gas. The present invention performs two-step anisotropic etching process on the upper and lower parts of the substrate, maintaining high anisotropic etching characteristics during a period ranging from an early state to a last state of the etching process, thereby enabling a fabrication of a probe tip having a peak of a minimized radius and a maximized height.